

# 7<sup>th</sup> IEEE Electron Devices Technology and Manufacturing (EDTM) Conference 2023

March 7 - 10, 2023 / COEX Seoul, Korea

41G. TCAD for Nano-Scale FET							
Session Date:	March 9(Thu.), 2023						
Session Time:	14:45-16:10						
Session Room:	Room G (#318)						
Session Chair:	Prof. Rock-Hyun Baek (Pohang University of Science and Technology)						

## [41G-1] [Invited]

### Deep Learning for Semiconductor Materials and Devices Design

Changwook Jeong<sup>1</sup>, Sanghoon Myung<sup>2</sup>, Byungseon Choi<sup>2</sup>, Jinwoo Kim<sup>2</sup>, Wonik Jang<sup>2</sup>, In Huh<sup>2</sup>, Jae Myung Choe<sup>2</sup>, Young-Gu Kim<sup>2</sup> and Dae Sin Kim<sup>2</sup>

<sup>1</sup>Ulsan National Institute of Science and Technology, <sup>2</sup>Samsung Electronics Co., Ltd.

#### [41G-2]

Optimization of Ge Mole Fraction in Sacrificial Layers for Sub-3-nm Node Silicon Nanosheet FETs

Sanguk Lee, Jinsu Jeong, Jun-Sik Yoon, Seunghwan Lee, Junjong Lee, Jaewan Lim and Rock-Hyun Baek

Pohang University of Science and Technology

[41G-3]	15:25-15:40
Investigation of Self-Heating Effect in Forksheet FETs for Sub-3-nm Node	
Jaewan Lim, Jinsu Jeong, Junjong Lee, Seunghwan Lee, Sanguk Lee and Rock-Hyu	n Baek

Pohang University of Science and Technology

[41G-4	4]									1	5:40	-15:5	55
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Process Condition Effects on Saddle Fin Profile and Its Device Performance below 20nm Advanced DRAM

Yexiao Yu, Zhongming Liu and Hong Ma

ChangXin Memory Technologies, Inc.

### [41G-5]

Process-Induced Uniaxial Strain in Nanosheet-FET Based CMOS Technology – Is It Still **Beneficial?** 

Ramandeep Kaur and Nihar R. Mohapatra Indian Institute of Technology Gandhinagar 15:55-16:10

14:45-15:10

15:10-15:25